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(54) Title: A POLISHING CLOTH AND A METHOD FOR ATTACHING/DETACHING THE POLISHING CLOTH TO/FROM A BASE PLATE OF A POLISHING MACHINE

(57) Abstract

A polishing cloth according to the present invention includes: a polishing cloth substrate (1); a pressure-sensitive adhesive layer (2) laminated on one face of the polishing cloth substrate (1); and a release sheet (3) attached to the pressure-sensitive adhesive layer (2) in a releasable manner. The pressure-sensitive adhesive layer (2) includes an adhesive composition containing a polymer, the polymer having a first-order melt transition in a temperature range narrower than 15 °C. Thus, the present invention provides a polishing cloth and a method for attaching/detaching the polishing cloth to/from a base plate of a polishing machine such that the polishing cloth can be peeled off the base plate by simply cooling the base plate and the adhesive layer of the polishing cloth.

